

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Narwankar, et al.

Application No.: 10/772,893

Filed: February 4, 2004

For: TAILORING NITROGEN PROFILE
IN SILICON OXYNITRIDE USING
RAPID THERMAL ANNEALING WITH
AMMONIA UNDER ULTRA-LOW
PRESSURE

Examiner: Stouffer, Kelly M.

Art Unit: 1792

Confirmation No.: 5371

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY UNDER 37 CFR §1.116 EXPEDITED PROCEDURE

Dear Examiner:

This is in response to the Final Office Action mailed November 24, 2008.

Applicants respectfully request the Examiner to enter this Amendment and consider the following remarks.

The Listing of Claims begins on page 2 of this paper.

Remarks/Arguments begin on page 11 of this paper.

I hereby certify that this correspondence is being deposited via
EFS Web on the date below:

January 26, 2009
Date of Deposit

/Gigi Hoover/
Gigi Hoover